



OBRA Molecular sieve 3Å

is a crystalline, high porous potassium aluminosilicate. Gas, vapours and liquids can be adsorbed reversibly or separated selectively due to the special crystal lattice with absolutely uniform, spherical cavities which are connected by channels. The large internal surface area of 600 – 700 m²/g and polar characteristics of the molecular sieve structure result in a stronger bond of adsorption. The pore openings are approx. 3Å across - larger molecules cannot be adsorbed, smaller molecules are.

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is used in various applications, such as the purification of gas, the drying of steam and liquids and the removal of water from air. OBRA molecular sieve 3Å has been particularly developed for use in manufacture of insulating glass. Because of pore diameter of approx. 3Å, the molecular sieve does not uptake nitrogen, argon or SF₆. Therefore OBRA molecular sieve 3Å is recommended for air-filled as well as for gas-filled insulating glass units.

Basis

Formula	Na ₁₂ [(AlO ₂) ₁₂ (SiO ₂) ₁₂] · 12 H ₂ O	CAS-No.	1318 – 02 – 1
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Characteristics

Adsorption capacity at 40% rel.Humidity	min. 18.5 %	Moisture loss (1h, 550°C)	max. 1.5 %
Bulk density	min. 720 g/l	Grain size	0.7 – 2.0 mm on request

Packaging

Cardboard box	with polyethylene bags at 25 kg
Steel drum	with polyethylene bags at 125 kg
Big Bags	with polyethylene Inliner at 600 kg

Note

Any details of application possibilities do not free the purchaser from the obligation of performing their own tests on the material supplied by the seller, in order to determine their suitability for the intended processes and purposes. Application, use and processing of the material cannot be controlled by the seller and are thus the sole responsibility of the purchaser.

OBRA molecular sieve 3Å must always be kept in airtight containers to avoid adsorption with water vapour. Face masks should be used at continual exposure to extensive dusting.